

FIG.1

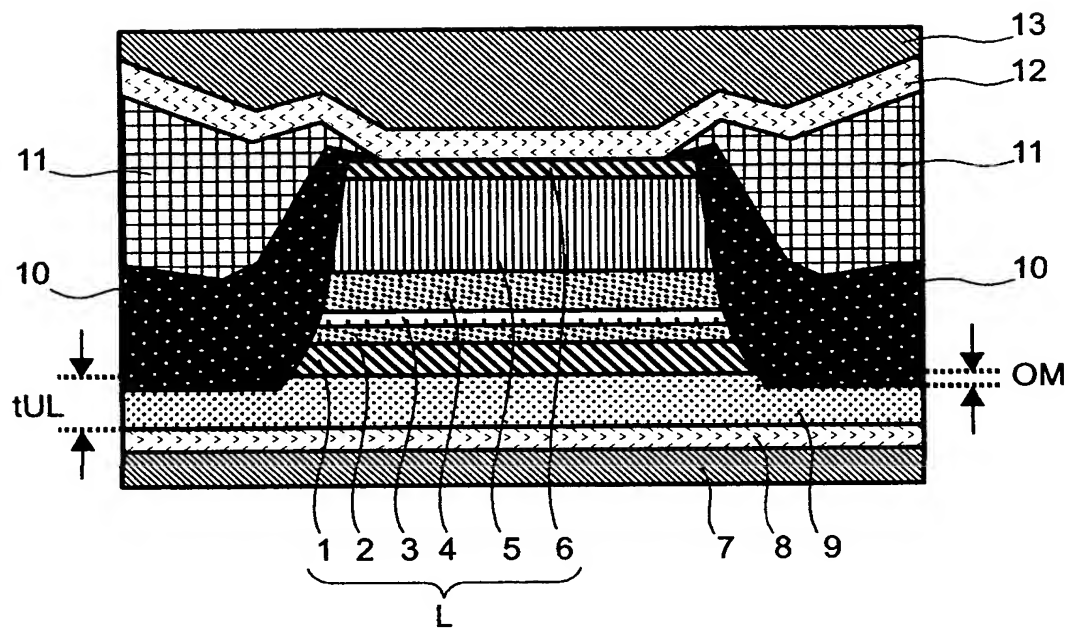


FIG.2

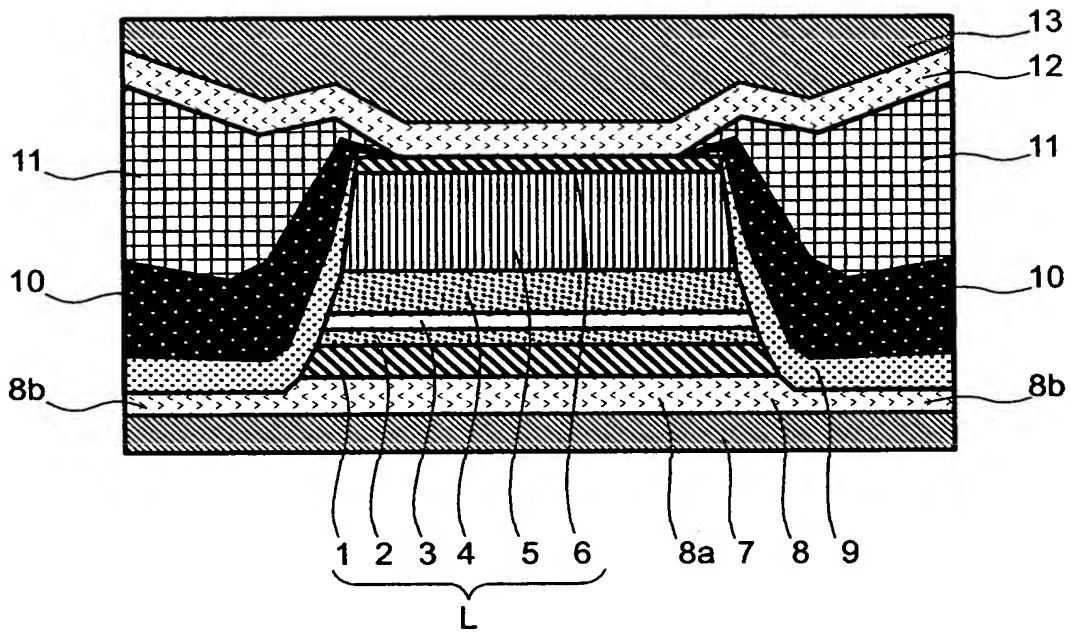


FIG.3

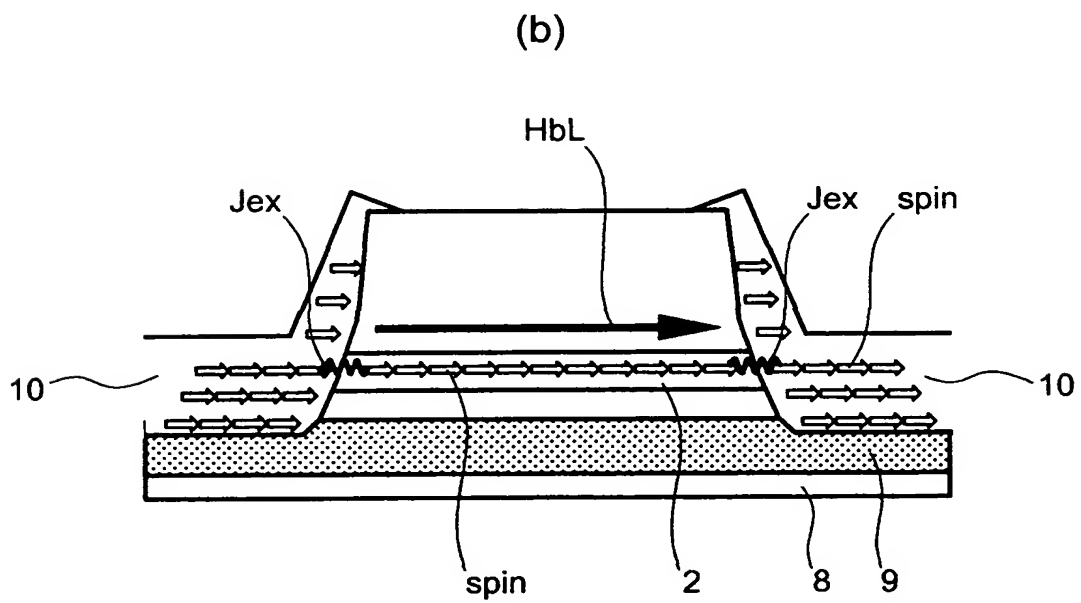
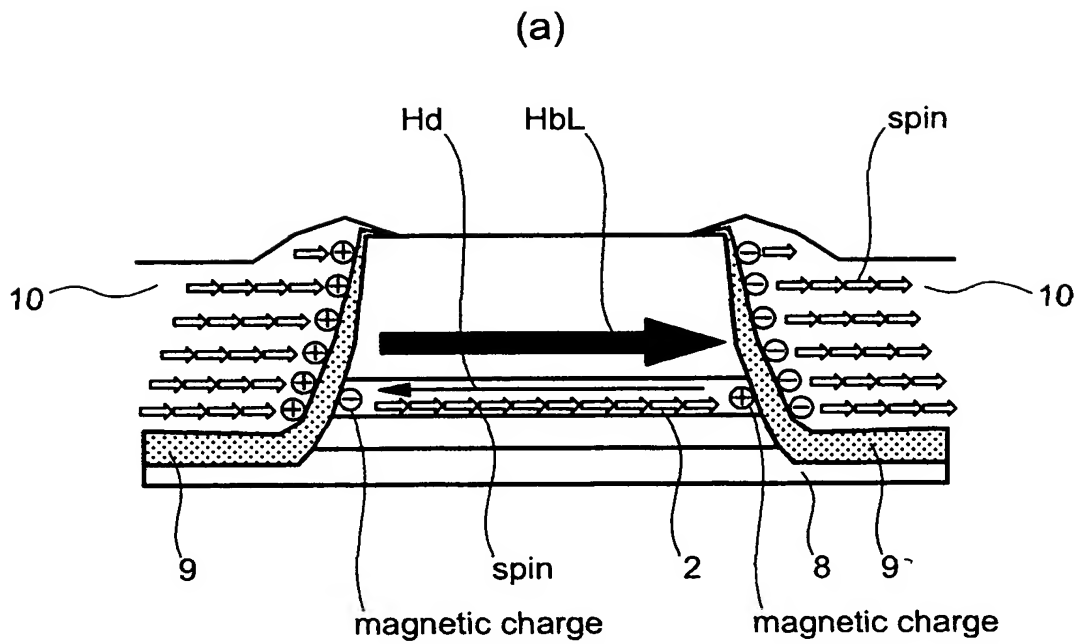


FIG.4

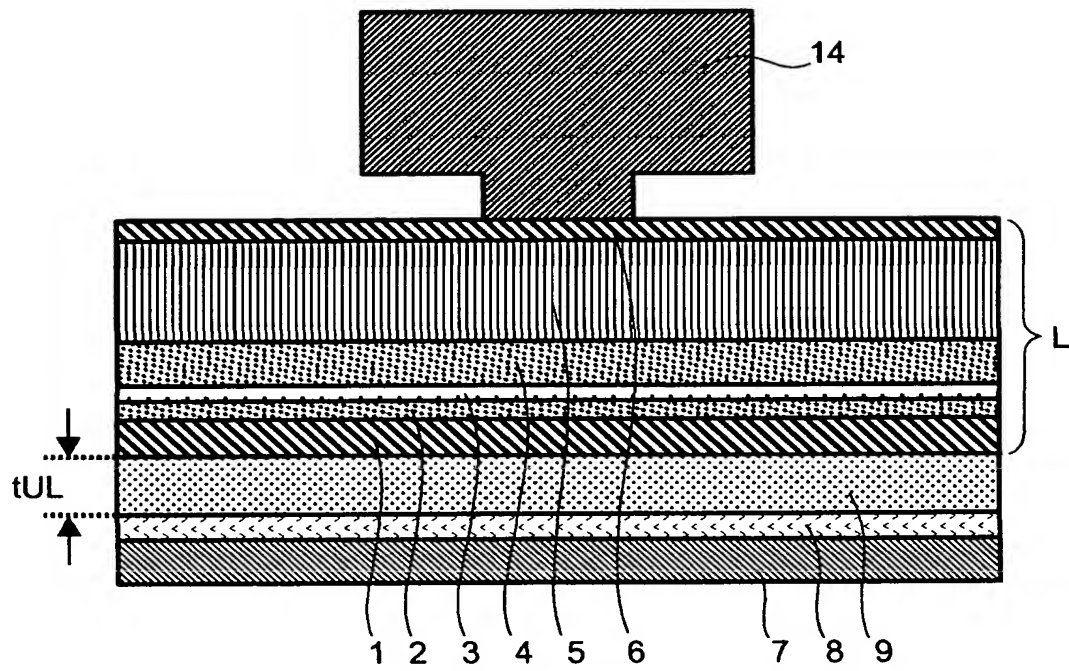


FIG.5

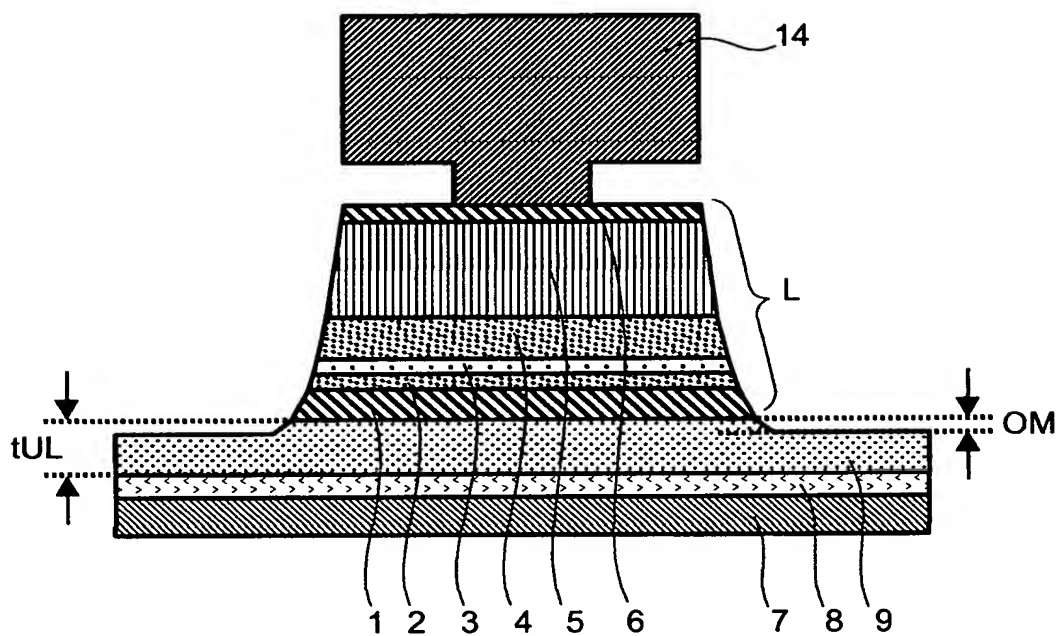


FIG.6

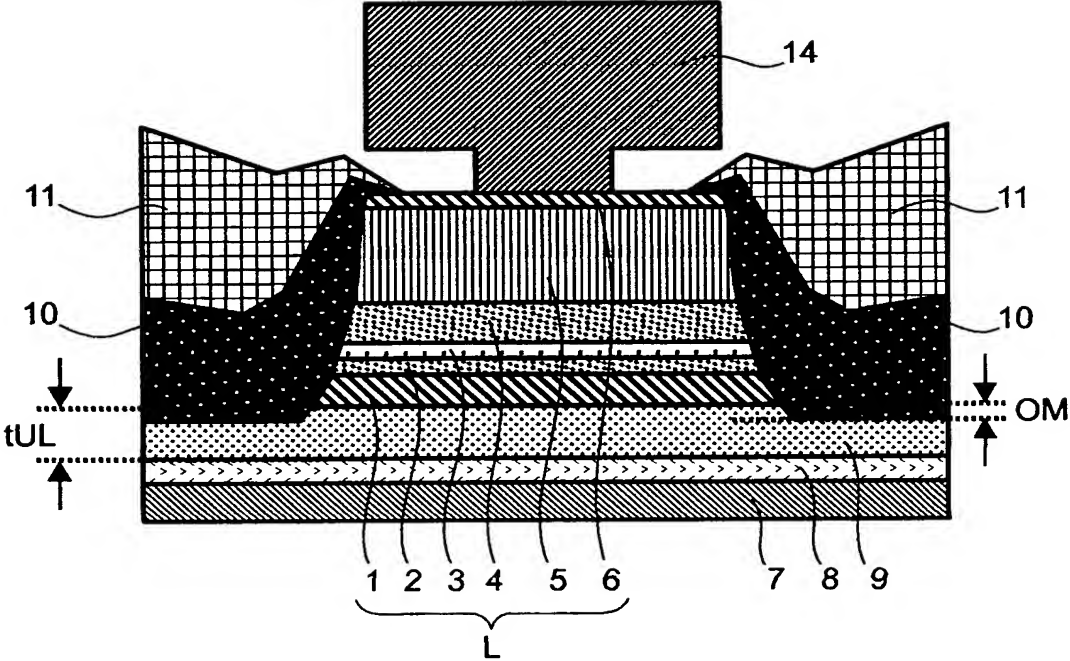


FIG.7

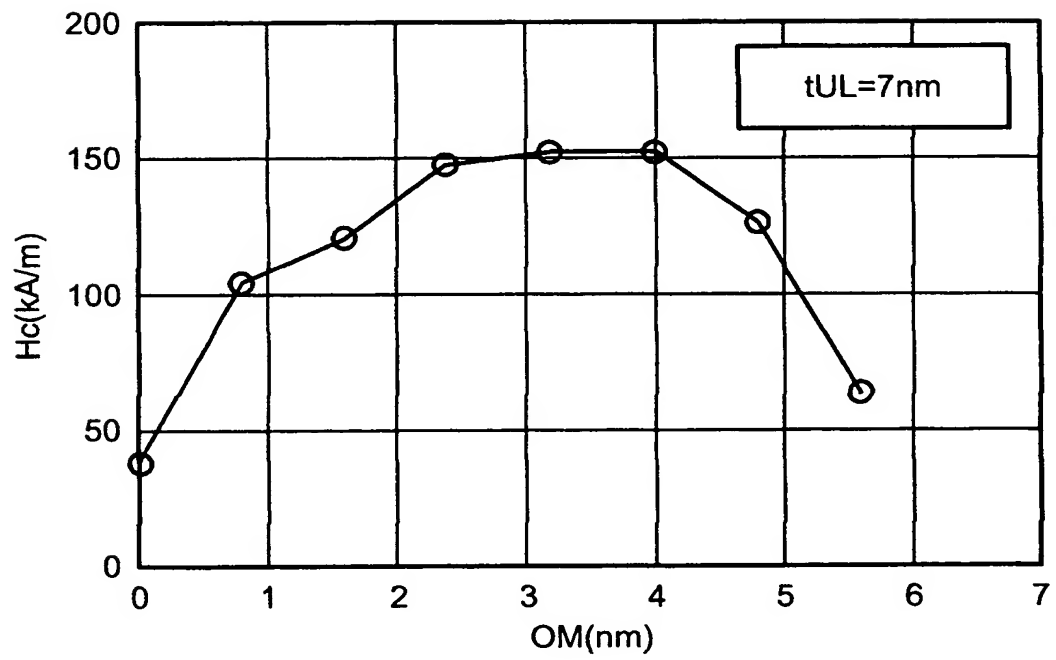
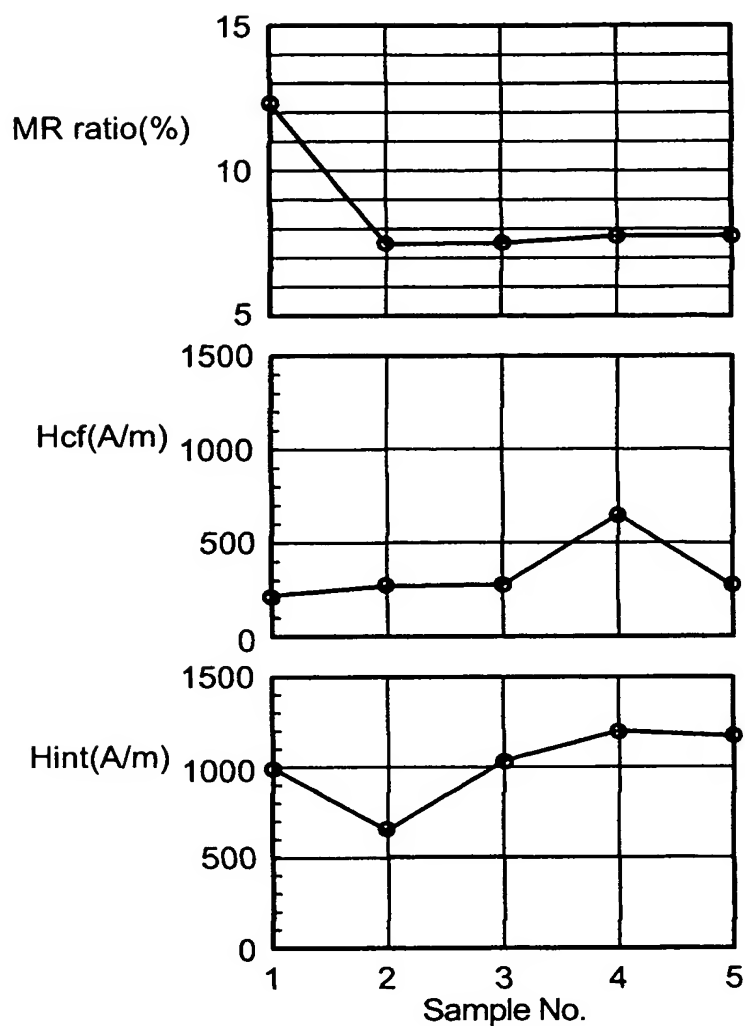


FIG.8



Sample No.	Magnetic domain control underlayer	Pretreatment for underlayer deposition	Underlayer
1	-	Atmospheric exposure	Underlayer A
2	Cr 10nm	Atmospheric exposure	Underlayer A
3	Cr 10nm	Atmospheric exposure	Ta 1 nm → Atmospheric exposure → underlayer A
4	Cr 10nm	Atmospheric exposure → plasma oxidation	Underlayer A
5	Cr 10nm	Atmospheric exposure → plasma oxidation	Ta 1 nm → Atmospheric exposure → underlayer A

FIG.9

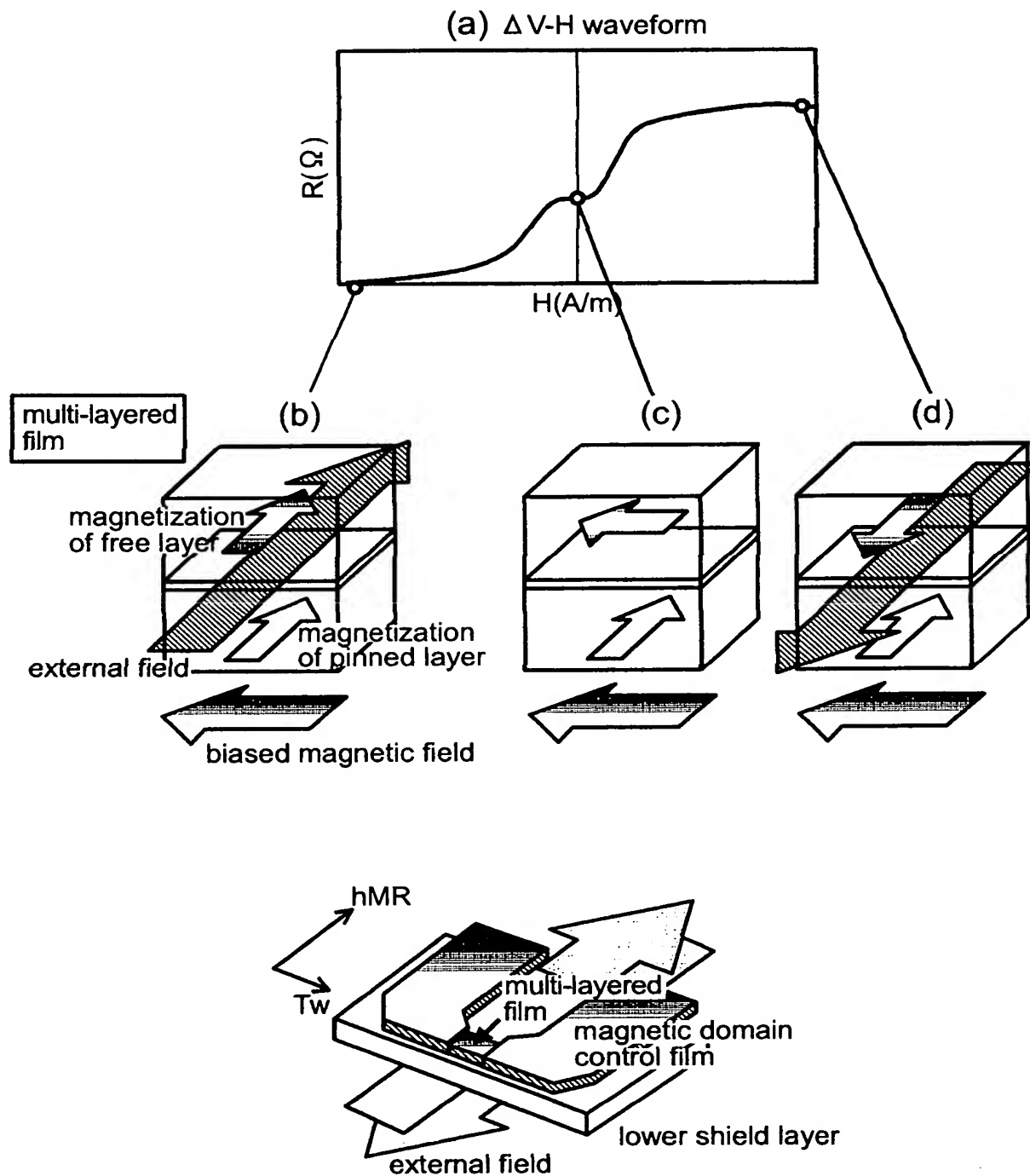
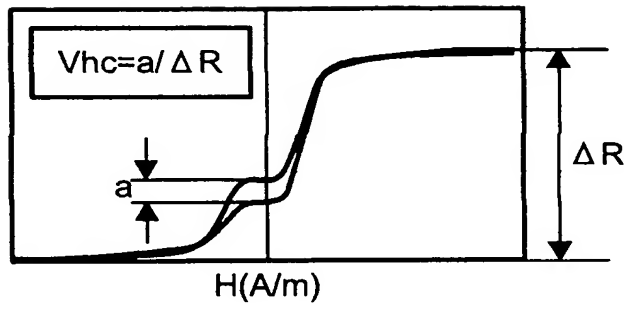
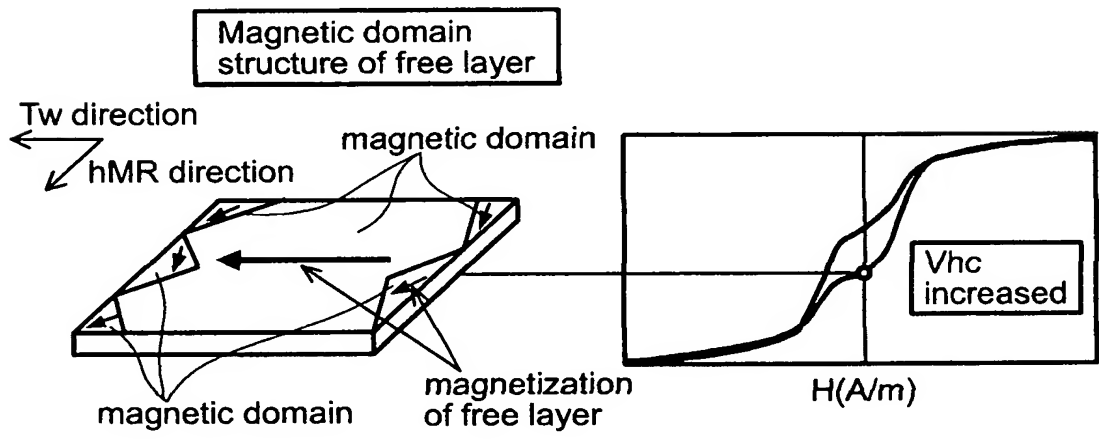


FIG.10



(a)



(b)

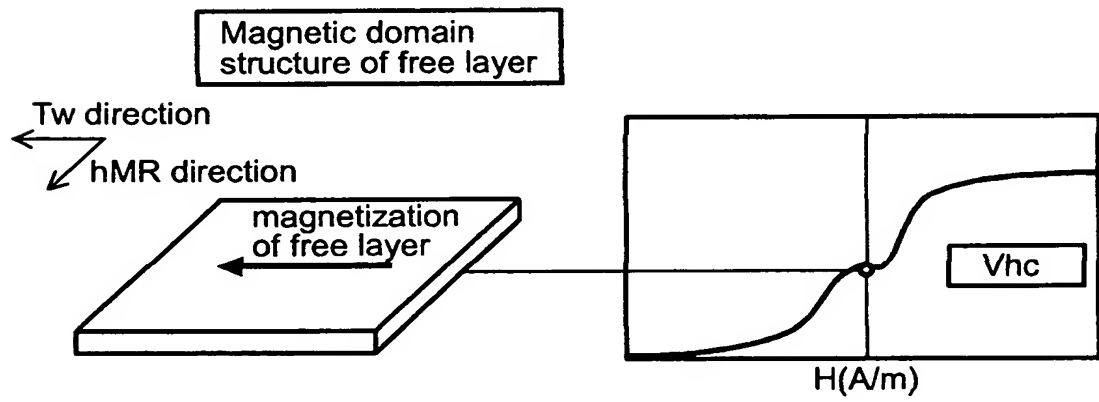


FIG.11

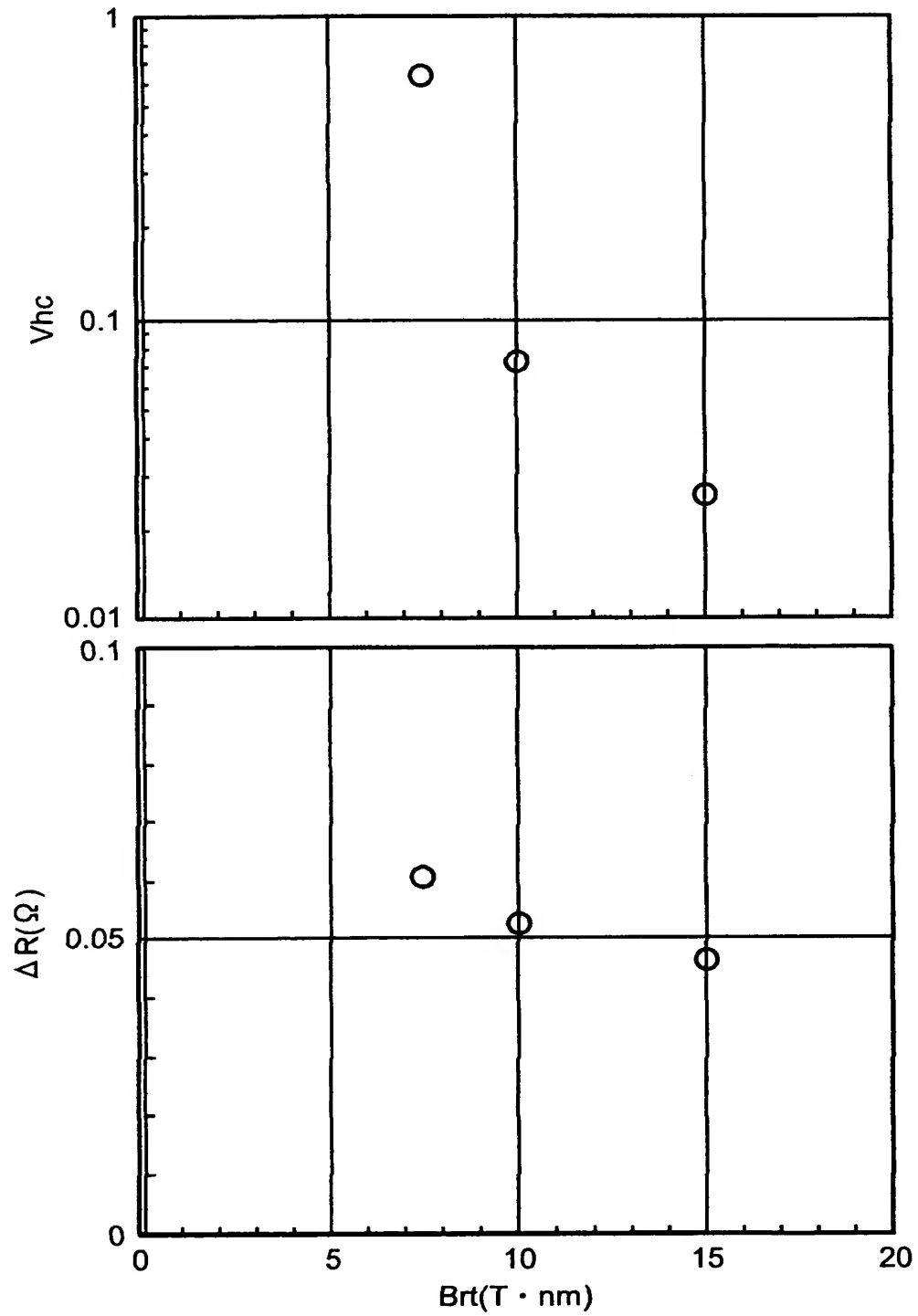


FIG.12

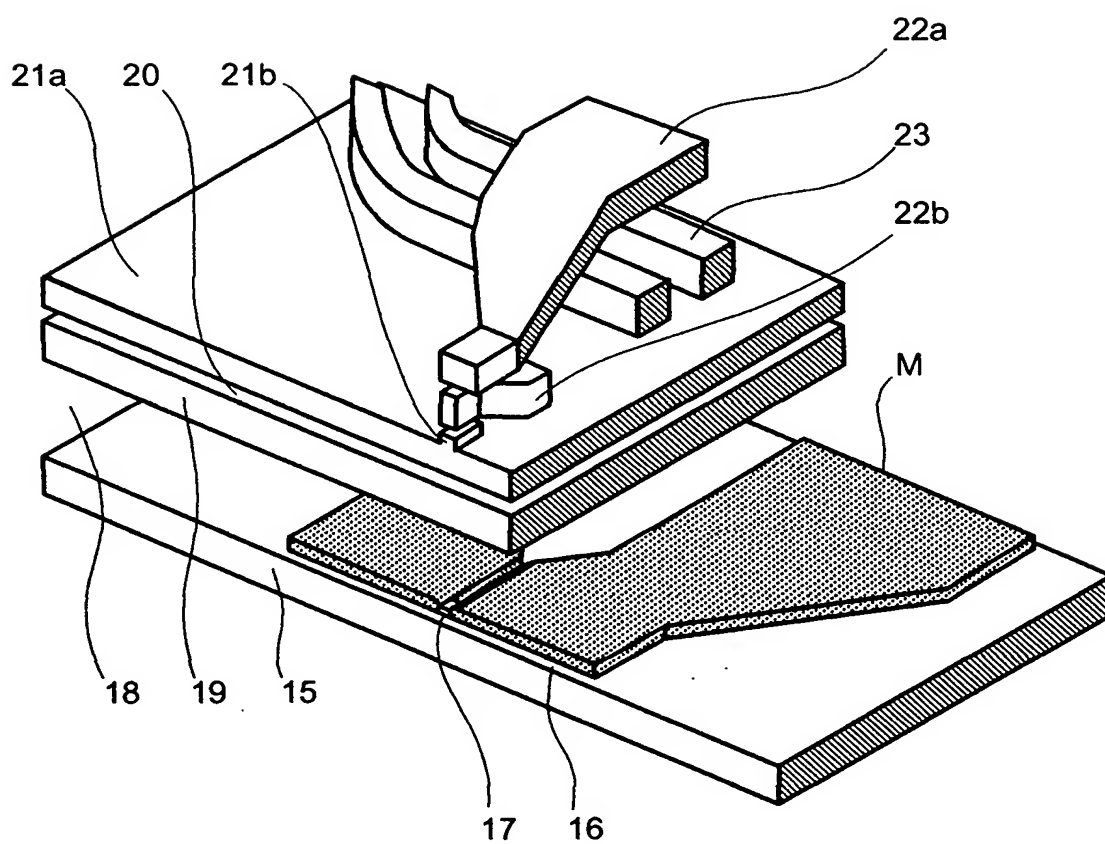


FIG.13

